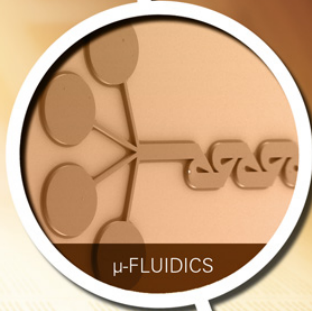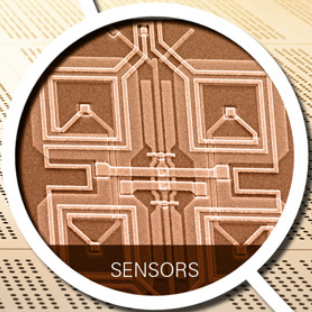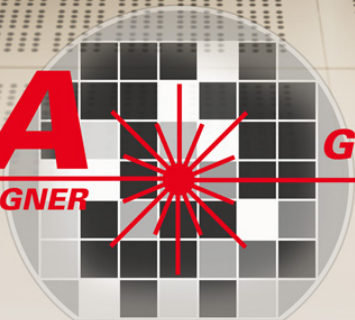MLA**150**

HEIDELBERG
iNSTRUMENTS

MEMS

DOE

μ-FLUIDICS

SENSORS

MLA
MASKLESS ALIGNER

GO MASKLESS
ACHIEVE MORE

MLA150

Hrs. Min.
00:03

STEP 1: SYSTEM SETUP
- Intuitive User Interface
- Multi-user capabilities
- Support for all standard input formats (dxf, gdsii, cif, gerber)
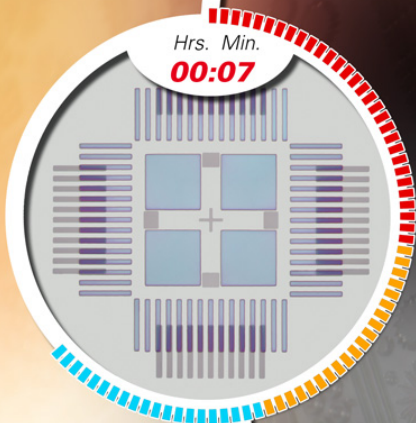- CAD Software for design creation included
- Resist database

Hrs. Min.
00:05

STEP 2: LOADING
- Simple loading procedure
- One chuck for all substrates from 5 x 5 mm² to 150 x 150 mm²
- Automatic substrate size detection
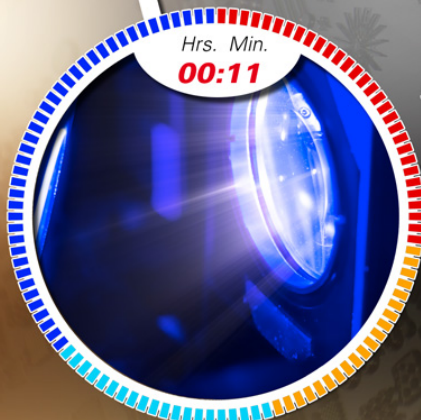- No need for edge-bead removal or wedge compensation

Hrs. Min.
00:07

STEP 3: ALIGNMENT
- High precision topside and backside alignment
- Fast alignment procedure
- Distortion compensation
- Simple alignment on thick resists and small substrates
- Alignment accuracy ≤ 500 nm

Hrs. Min.
00:11

STEP 4: EXPOSURE
- Min. feature size of 1μm
- Exposure time for 50 x 50 mm² approx. 4 min.
- Non-contact exposure
- High Aspect Ratio exposures in thick resist
- Automatic labeling and serialization
- Compatible to g-, h- and i-line resists

MLA MASKLESS ALIGNER

GO MASK*LESS*
ACHIEVE MORE